2016 Source Workshop

Keynote Presenter

Hans Hertz

Hertz received his Ph.D. in optical physics 1988 at Lund University, Sweden and did his post-doc at Dept. of Applied Physics, Stanford University. Since 1997 he is a professor in Biomedical Physics at the Royal Inst. of Technol. (KTH), Stockholm. Here he leads a ☐30 person cross-disciplinary research group with focus on x-ray science and technology including optics, nanoparticles, ultrasonics, and bioengineering.

He pioneered the liquid-jet laser-plasma source, the liquid-metal-jet electron-impact source and laboratory x-ray microscopy, and the research has resulted in a few spin-off companies. His present research interests include x-ray sources and x-ray optics, high-resolution phase-contrast x-ray imaging, x-ray fluorescence imaging, and x-ray microscopy. From 2006 to 2012 he was the first head of the Dept. of Applied Physics. In spring 2013 he was a visiting professor at Dept. of Radiology, Stanford University and in fall 2014 he was a fellow at Stellenbosch Inst. of Advanced Studies, South Africa. He is presently chairman of the Board of the MAX IV Laboratory (Lund) and Excillum AB (Stockholm). He is a fellow of the Royal Academy of Sciences (KVA) and the Royal Swedish Academy of Engineering Sciences (IVA). He has published >140 scientific papers, holds >25 patents, and has advised >25 PhDs.

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